

AB

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 06-076282

(43)Date of publication of application : 18.03.1994

(51)Int.Cl.

G11B 5/84
B23K 26/00
H01L 21/304

(21)Application number : 04-253773

(71)Applicant : SHIN ETSU CHEM CO LTD
NAGANO DENSHI KOGYO KK
SHIN ETSU HANDOTAI CO LTD

(22)Date of filing : 28.08.1992

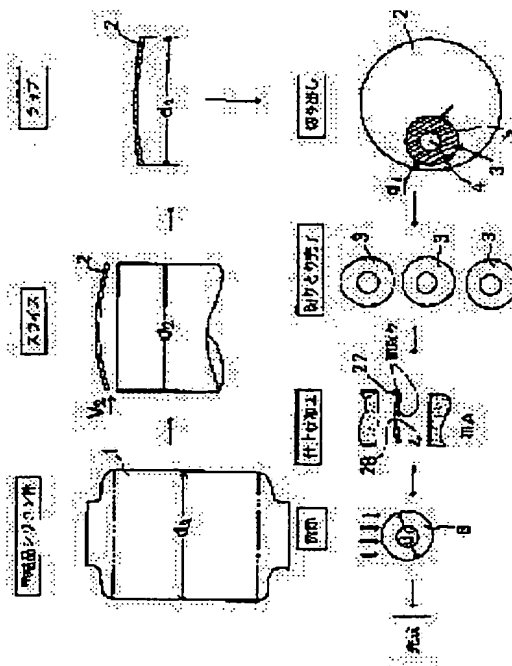
(72)Inventor : KANEKO HIDEO
NAKAZATO YASUAKI
AOKI TOYOFUMI
KUROYANAGI ITSUO

(54) METHOD AND APPARATUS FOR PRODUCTION OF MAGNETIC RECORDING MEDIUM SUBSTRATE

(57)Abstract:

PURPOSE: To produce the magnetic recording medium substrate, such as substrate for a magnetic disk, which maintains high flatness and concentricity with high efficiency without variations.

CONSTITUTION: A wafer 2 is formed by slicing a single crystal silicon rod 1 of a large diameter (diameter d_2) at a high speed of a slicing speed $V_2 > V_1$. Plural sheets of doughnut-shaped disks 3 each having a central hole 4 and a small diameter (diameter d_1) are cut out of this wafer and are finished, by which finished products are produced. The cutting out is executed by irradiating the central hole 4 of the cut out disk 3 and edge parts 27, 28 of the outer periphery thereof with a laser beam and rotating the wafer 2 around the central hole 4 at its center. The positioning of the cutting out position of the disk 3 to be cut out is executed by turning the wafer 2 to a prescribed indexing angle position. Where, V_1 denotes the sliding speed necessary for generating the warpage of a prescribed value or below from the single crystal silicon rod of the diameter (diameter d_1).



LEGAL STATUS

[Date of request for examination]

20.03.1996

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

USPS EXPRESS MAIL

EV 636 851 726 US

OCT 03 2005